

	L #	Hits	Search Text	DBs
1	L1	1284	430/321.ccls.	US-PGPUB; USPAT
2	L2	16910	waveguide.ti,ab.	US-PGPUB; USPAT
3	L3	112	1 and 2	US-PGPUB; USPAT
4	L4	278559	(polymer or organic or polymeric or photosensitiv\$6 or photopolymeri\$6 or photoresist or polymeriz\$6 or polymeris\$6 or resist).ti,ab.	US-PGPUB; USPAT
5	L5	970	2 and 4	US-PGPUB; USPAT
6	L8	142	(oxygen\$6 or deoxygen\$6 or o2 or "o.sub.2") same (vacuum or pressure or inert or gas) and 5	US-PGPUB; USPAT
7	L9	57570	(partial\$4 or incomplet\$6 or full\$4) with (polymeriz\$6 or polymeris\$6 or cure\$1 or curing or harden\$4)	US-PGPUB; USPAT
8	L10	116	5 and 9	US-PGPUB; USPAT
9	L11	1961	385/129,130.ccls.	US-PGPUB; USPAT
10	L12	531	385/143,145.ccls.	US-PGPUB; USPAT
11	L13	225945	(photosensitiv\$6 or photopolymer\$6 or photoresist or expos\$4 or irradiat\$4 or radiat\$4).ti,ab.	US-PGPUB; USPAT
12	L14	271	11 and 4	US-PGPUB; USPAT
13	L15	201	14 not (3 or 8 or 10)	US-PGPUB; USPAT
14	L16	220762	liquid.ti,ab.	US-PGPUB; USPAT

	L #	Hits	Search Text	DBs
15	L17	56	2 and 4 and 16	US-PGPUB; USPAT
16	L18	99	12 and 13	US-PGPUB; USPAT
17	L19	300534	proximity	US-PGPUB; USPAT
18	L20	1966	2 and 19	US-PGPUB; USPAT
19	L21	27675	19 with (imag\$4 or expos\$4 or mask\$4 or photomask\$4 or reticle or pattern\$4 or photolith\$10 or lithograph\$6 or radiat\$4 or irradiat\$4)	US-PGPUB; USPAT
20	L22	293	2 and 21	US-PGPUB; USPAT
21	L23	19685	19 near8 (imag\$4 or expos\$4 or mask\$4 or photomask\$4 or reticle or pattern\$4 or photolith\$10 or lithograph\$6 or radiat\$4 or irradiat\$4)	US-PGPUB; USPAT
22	L24	45	5 and 23	US-PGPUB; USPAT
23	L26	338342	mask\$4 or photomask\$4 or reticle	US-PGPUB; USPAT
24	L27	530110	oxygen\$6 or deoxygen\$6 or o2 or "o.sub.2"	US-PGPUB; USPAT
25	L29	9767	26 with 27	US-PGPUB; USPAT
26	L30	25	5 and 29	US-PGPUB; USPAT
27	L31	75733	waveguide	EPO; JPO; DERWE NT; IBM_TDB

	L #	Hits	Search Text	DBs
28	L32	2122162	polymer or organic or polymeric or photosensitiv\$6 or photopolymeri\$6 or photoresist or polymeriz\$6 or polymeris\$6 or resist	EPO; JPO; DERWE NT; IBM_TDB
29	L33	261884	mask\$4 or photomask\$4 or reticle	EPO; JPO; DERWE NT; IBM_TDB
30	L34	347608	oxygen\$6 or deoxygen\$6 or o2 or "o.sub.2"	EPO; JPO; DERWE NT; IBM_TDB
31	L35	41	31 and 32 and 33 and 34	EPO; JPO; DERWE NT; IBM_TDB
32	L36	57487	proximity	EPO; JPO; DERWE NT; IBM_TDB
33	L37	36	31 and 32 and 36	EPO; JPO; DERWE NT; IBM_TDB
34	L40	12	ferm-paul\$.in.	US- PGPUB; USPAT
35	L41	3	battell-kevin\$.in.	US- PGPUB; USPAT
36	L42	44	beeson-karl\$.in.	US- PGPUB; USPAT

	L #	Hits	Search Text	DBs
37	L43	22	maxfield-macrae\$.in.	US- PGPUB; USPAT
38	L44	6	pant-deepti\$.in.	US- PGPUB; USPAT
39	L45	55	shacklette-lawrence\$.in.	US- PGPUB; USPAT
40	L46	45	(37 or 40 or 41 or 42 or 43 or 44 or 45) and 2	US- PGPUB; USPAT